



Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. Intel 10559-865001 / P17313	Application No. 10/649,355
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))      IDS filed 09/22/2003		Applicant Florence Eschbach et al.	
		Filing Date August 26, 2003	Group Art Unit 1713

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AH							
	AI							
	AJ							
	AK							
	AL							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
HLS	AM	D.W. Van Krevelen, with the collaboration of P.J. Hoftyzer; "Properties of Polymers, Their Estimation and Correlation with Chemical Structure," Second, completely revised edition; 1976, Elsevier Scientific Publishing Company, Amsterdam - Oxford - New York
	AN	Oshima et al.; Radiation Physics and Chemistry, "Chemical structure and physical properties of radiation-induced crosslinking of polytetrafluoroethylene"; © 2001 Elsevier Science Ltd.; <a href="http://www.elsevier.com/locate/radphyschem">www.elsevier.com/locate/radphyschem</a>
	AO	Reu et al.; "Mechanical analysis of hard pellicles for 157 nm lithography," to appear in the Proceedings of the 2001 SPIE Symposium on Optical Microlithography XIV, Vol. 4346, 2001; UW Computational Mechanics Center, University of Wisconsin, Madison, WI 53706; Intel Corporation, Santa Clara, CA 95052
	AP	Kozeki et al.; "Longevity of 193nm/ArF Excimer Pellicle; April 26, 2001; Mitsui Chemicals, Inc., Pellicles Dept.
✓	AQ	Shu et al.; "Hard Pellicle Study for 157-nm Lithography"; Preprint, to appear in the Proceedings of Photomask Japan, 2002

Examiner Signature 	Date Considered 4-10-06
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	